

Title (en)  
METHOD FOR PRODUCING GLASS SUBSTRATE WITH SILICON OXIDE FILM CONTAINING INORGANIC FINE PARTICLES

Title (de)  
VERFAHREN ZUR HERSTELLUNG EINES GLASSUBSTRAT MIT EINER SILICIUMOXIDSCHICHT MIT FEINEN ANORGANISCHEN TEILCHEN

Title (fr)  
PROCÉDÉ DE FABRICATION DE SUBSTRAT DE VERRE AVEC FILM D'OXYDE DE SILICIUM COMPRENANT DES MICROPARTICULES INORGANIQUES

Publication  
**EP 2842920 A1 20150304 (EN)**

Application  
**EP 13781896 A 20130423**

Priority  
• JP 2012099166 A 20120424  
• JP 2013061947 W 20130423

Abstract (en)  
To provide a process for producing a glass substrate provided with an inorganic fine particle-containing silicon oxide film, wherein inorganic fine particles having a desired particle size may be used depending on intended optical properties, and the range of selection of the inorganic fine particles is wide. A process for producing a glass substrate provided with an inorganic fine particle-containing silicon oxide film, which comprises applying a coating liquid containing inorganic fine particles 14, a hydrolysate of an alkoxysilane, and one of or both water and a (poly)ethylene glycol, to a glass substrate 10 to form an inorganic fine particle-containing silicon oxide film 12; or which comprises forming molten glass into a glass ribbon, annealing the glass ribbon, and at the time of cutting the glass ribbon to obtain a glass substrate, applying a coating liquid containing inorganic fine particles, a hydrolysate of an alkoxysilane, and one of or both water and a (poly)ethylene glycol, to the glass ribbon to form an inorganic fine particle-containing silicon oxide film.

IPC 8 full level  
**C03C 17/25** (2006.01); **C03C 17/34** (2006.01); **G02B 5/02** (2006.01); **H01L 31/04** (2006.01); **H01L 51/50** (2006.01); **H05B 33/02** (2006.01)

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